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Form PTO-1449		U.S. Department of Commerce Patent & Trademark Office		Atty. Docket No.: 622/43770		Serial No.: 08/928,652	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				Applicants: Hans BRAENDLE et al.		Group	
				Filing Date: September 12, 1998			
U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
	AA						
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FOREIGN PATENT DOCUMENTS							
		Document	Date	Country	Class	Sub-class	Translation Yes No
GR	AK	0 701 982 A1		EPO			
ER	AL	0 448 720 A1		EPO			
BR	AM	08-209335		Japan			
	AN						
	AO						
	AP						
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
OR	AQ	Average Energy Deposited Per Atom: A Universal Parameter For Describing Ion-Assisted Film Growth; Petrov et al.; Applied Physics Letters, July 5, 1993, pp. 36-38					
1/27/93 GBR	AR	Titanium Aluminum Nitride Films: A New Alternative to TiN Coatings; Muenz; Journal Of Vacuum Science & Technology, Nov.-Dec. 1986, pp. 2717-2225					
1/27/93 GBR	AS	Interrelationship Between Processing, Coating Properties And Functional Properties Of Steered-ARC Physically Vapour Deposited (Ti,Al)N And (Ti,Nb)N Coatings; Roos et al.; Elsevier Sequoia; December 1, 1990; pp. 547-556					
EXAMINER				DATE CONSIDERED 3/15/07			
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	AL						
	AM						
	AN						
	AO						
	AP						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
GDR	AQ	Effects Of R.F. Bias And Nitrogen Flow Rates On The Reactive Sputtering Of TiAlN Films; Shew et al.; Elsevier; 1997; pp. 212-219
GDR	AR	Effects of High-Flux Low-Energy (20-100 eV) Ion Irradiation During Deposition On The Microstructure And Preferred Orientation of $Ti_{0.5}Al_{0.5}N$ Alloys Grown By Ultra-High-Vacuum Reactive Magnetron Sputtering; Adibi et al.; Journal of Applied Physics, June 15, 1993; pp. 8580-8589
GDR	AS	The Structure And Composition Of Ti-Zr-N, Ti-Al-Zr-N and Ti-Al-V-N Coatings, Knotek et al.; Materials Science and Engineering, 1988; pp. 481-488

EXAMINER [Signature]

DATE CONSIDERED 3/15/01

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